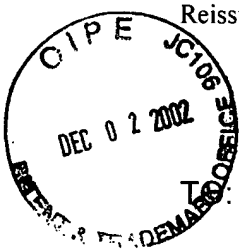


TSMC97-306
Reissue Application no. 10/062,314

Reissue Application of Patent no. 6,019,906

1754



November 19, 2002

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FROM: George O. Saile, Reg. No. 19,572
20 McIntosh Drive
Poughkeepsie, N.Y. 12603

SUBJECT: **Reissue Application of:**
Patent #: 6,019,906
Issue Date: Feb. 1, 2000
Inventor: Syun-Ming Jang, Ming-Hsin Huang
Title: Hard Masking Method for Forming Patterned Oxygen
Containing Plasma Etchable Layer

Reissue Serial Number: **10/062,314**
Reissue File Date: **Feb. 1, 2002**

RESPONSE TO OFFICE ACTION

This is in response to the office action dated August 23, 2002. Please amend the
above-identified Reissue application for patent as follows:

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States
Postal Service as first class mail in an envelope addressed to: Commissioner of
Patents and Trademarks, Washington, D.C. 20231 on November 25, 2002.

Signature 
Stephen B. Ackerman, Reg. No. 37,761

Date: 11/25/02